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Supporting Information

A Silanol-Functionalized Polyoxometalate with Excellent Electron Transfer Mediating Behavior to ZnO and TiO₂ Cathode Interlayers for Highly Efficient and Extremely Stable Polymer Solar Cells

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Additional Figures



Figure S1 (a) FTIR spectrum of tBuSiOH-POM. For the POM part, the bands at 1100 cm⁻¹ and 1034 cm⁻¹ are assigned to the P-O stretching modes of the central PO₄ tetrahedron.¹ At 1003 cm⁻¹, 969 cm⁻¹, 940 cm⁻¹ appear bands corresponding to W=O modes and at 864 cm⁻¹, 835 cm⁻¹, 727 cm⁻¹ corresponding to W-O-W stretching modes, while the bands at 389 cm⁻¹ and 345 cm⁻¹ are considered as the α isomer signature.² The bands at 810 cm⁻¹ and 1080 cm⁻¹ are assigned to Si-O bending and stretching modes while the band at 1487 cm⁻¹ is assigned to C-C stretching mode.³ In the high-frequency part, the typical broad-band pattern at 3400 cm⁻¹ is characteristic of the –OH stretching of Si-OH or adsorbed water molecules.⁴ (b) Absorption spectrum of tBuSiOH-POM in an acetonitrile solution.



Figure S2 (a) ³¹P NMR and (b) ¹H NMR spectra of tBuSiOH-POM: The ³¹P NMR spectrum depends on the saturation state of the polyoxometalate.⁵ In the case of tBuSiOH-POM, the signal for the phosphorus atoms is found at δ =-15.85 ppm. For a complete structural analysis in solution of tBuSiOH-POM, ¹H NMR spectroscopy has been performed in CD₃CN. In addition to the [nBu₄N]⁺ resonances, the ¹H NMR spectrum of tBuSiOH-POM displays assigned to the Si-OH and tBuSi moieties respectively. The relative integration of these signals compatible with the formula, that are three tBuSiOH groups grafted on a [PW₉O₃₄]⁹⁻ anion and there are [nBu₄N]⁺ cations.^{6,7.}



Figure S3 (a) Cyclic voltammogram of tBuSiOH-POM at glassy carbon electrode. The concentration of tBuSiOH-POM was 10^{-3} mol L⁻¹ in a acetonitrile solution with 10^{-1} mol L⁻¹ Bu₄NBF₄ as supporting electrolyte. Scanning rate: 100 mV/s. The cyclic voltammetry data of the tBuSiOH-POM compound were collected with respect to Ag/Ag⁺ and the calculated LUMO energy level was -4.384 eV. Notably, each of the three polyoxotungstate hybrids [PW₉O₃₄ (tBuSiOH)₃]³⁻ displays three reversible waves. They correspond to one-electron redox processes as it is known to be the case for Keggin-type POMs in non-aqueous solvents when no protonation accompanies reduction.^{8,9} The reduction waves of tBuSiOH-POM are only slightly shifted to more negative potentials with respect to [PW₉O₃₄ (tBuSiOH)₃]³⁻. (b) Energy levels of POM as estimated from cyclic voltammetry and absorption measurements.



Figure S4 XPS W4f peaks of a tBuSiOH-POM thin film deposited on (a) TiO₂ and (b) ZnO substrates. The deconvolution of the W 4f photoemission peaks of tBuSiOH-POM on TiO₂ was performed using two distinct doublets with the major contribution coming from the doublet with peaks of nearly equal width with the binding energy (BE) of W 4f_{7/2} centered at 35.8 ± 0.1 eV and that of W 4f_{5/2} at a BE of 37.8 ± 0.1 eV (with a peak ratio of 4:3). The position and the shape of these peaks are representative of W atoms with an oxidation state +6.¹⁰ In addition, a second doublet at lower BEs (BE of W 4f_{7/2} = 34.5 eV, and of W 4f_{5/2} = 36.2 eV with a peak ratio 4:3) is also evident, which was attributed to the presence of W⁵⁺ ions, indicating that these films are reduced (exhibiting tungsten atoms with a valence of +5). The signal of tBuSiOH-POM on ZnO was very weak probably due to the nanoparticle-like surface morphology and the increased surface roughness of ZnO as compared to TiO₂.



Figure S5 XPS spectra acquired from TiO₂/tBuSiOH-POM interface of (a) Si2p and (b) N1s located at 102.0 eV and 401.9 eV BEs respectively. The signal of the corresponding XPS peaks of ZnO/tBuSiOH-POM interface was very weak and, therefore, they are not presented.



Figure S6 (a) Absorption spectra and (b) Tauc plots as derived from absorption measurements for TiO_2 (indirect gap) with and without the tBuSiOH-POM.



Figure S7 (a) Absorption spectra and (b) Tauc plots as derived from absorption measurements for ZnO (direct gap) with and without the tBuSiOH-POM.



Figure S8 Contact angle measurements of deionized water and diiodomethane drops on TiO_2 with and without tBuSiOH-POM.



Figure S9 Contact angle measurements of deionized water and diiodomethane drops on ZnO with and without tBuSiOH-POM.



Figure S10 The near Fermi level region of the UPS spectrum of TiO₂/tBuSiOH-POM interface.



Figure S11 (a) J-V characteristics under 1.5 AM illumination of P3HT:PC₇₁BM-based devices fabricated on FTO/TiO₂ or FTO/ZnO substrates without and with tBuSiOH-POM (see also Table S2). For the device fabrication P3HT:PC₇₁BM blends (10 mg mL⁻¹ for P3HT, 8 mg mL⁻¹ for PC₇₁BM in 1,2-dichlorobenzene) were spin coated at 600 rpm for 40 sec and annealed at 135 °C for 15 sec. (b) Dark J-V characteristics of the PSC devices without and with tBuSiOH-POM.



Figure S12 J-V characteristics under 1.5 AM illumination of PTB7:PC₇₁BM-based devices fabricated on FTO/TiO₂ or FTO/ZnO substrates without and with tBuSiOH-POM (see also Table S3). For the device fabrication PTB7:PC₇₁BM blends were deposited inside an argon filled glove-box via spin coating at 1000 rpm for 90 sec from solutions with concentrations of 10 mg mL⁻¹ for PTB7 and 15 mg mL⁻¹ for PC₇₁BM in 1,2-dichlorobenzene where 3% per volume of 1,8-diiodoctane (DIO) was added and was then left to dry for 30 min inside the glove box, without any post-deposition annealing. (b) Dark J-V characteristics of the PSC devices without and with tBuSiOH-POM.



Figure S13 (a) J-V characteristics under 1.5 AM illumination of P3HT:IC₆₀BA-based devices fabricated on ITO and ITO/tBuSiOH-POM substrates (see also Table S4). (b) Dark J-V characteristics of the PSC devices without and with tBuSiOH-POM.



Figure S14 Polyhedral molecular structure of the tBuSiOH-POM in gas phase, obtained via geometry optimization at the DFT-PBE level of theory.



Figure S15 Steady-state PL spectra of P3HT: $IC_{60}BA$ blends on as-deposited and tBuSiOH-POM-covered (a) TiO₂ and (b) ZnO films.

Additional tables

Substrate	θ _w (°)	θ _i (°)	γ _{sp} (mJ m ⁻²)	γ _{sd} (mJ m ⁻²)	γ(mJ m ⁻²)
TiO₂	45.0 (±2.0)	29.4 (±1.0)	22.93 (±0.53)	35.81 (±0.07)	58.74 (±0.40)
TiO ₂ /tBuSiOH-POM	52.1 (±1.8)	39.3 (±1.2)	20.40 (±0.75)	32.22 (±0.40)	52.62 (±0.45)
ZnO	46.7 (±2.1)	20.6 (±0.9)	20.21 (±0.71)	39.26 (±0.27)	59.47 (±0.43)
ZnO/tBuSiOH-POM	54.2 (±1.8)	29.4 (±1.0)	16.75 (±0.50)	37.18 (±0.30)	53.93 (±0.20)

Table S1 Surface energy as derived from contact angle measurements of TiO_2 and ZnO substrates without and with tBuSiOH-POM spin coated from a solution with concentration of 5 mg ml⁻¹.

TableS2. Device characteristics of polymer solar cells having the device configuration FTO/TiO_2 or ZnO without and with tBuSiOH-POM/P3HT:PC₇₁BM/MoO_x/AI (mean values and standard deviations were extracted from a batch of 8 independent devices).

ETL	J _{sc} (mA cm⁻²)	V _{oc} FF (V)		PCE (%)	R _s (Ω cm²)	R _{sh} (Ω cm²)
TiO ₂	9.43 (±0.11)	0.60 (±0.01)	0.56 (±0.01)	3.17 (±0.12)	3.9	1807
ZnO	9.80 (±0.10)	0.60 (±0.01)	0.58 (±0.01)	3.41 (±0.10)	2.8	1763
TiO ₂ /tBuSiOH-POM	10.60 (±0.15)	0.64 (±0.01)	0.65 (±0.01)	4.41 (±0.14)	2.1	2667
ZnO/ tBuSiOH-POM	10.80 (±0.12)	0.64 (±0.01)	0.64 (±0.01)	4.42 (±0.13)	1.9	2376

TableS3. Device characteristics of polymer solar cells having the device configuration FTO/TiO_2 or ZnO without and with tBuSiOH-POM/PTB7:PC₇₁BM/MoO_x/AI (mean values and standard deviations were extracted from a batch of 8 independent devices).

ETL	J _{sc} (mA cm ⁻²)	V _{oc} (V)	V _{oc} FF (V)		R _s (Ω cm ²)	R _{sh} (Ω cm²)
TiO ₂	14.24 (±0.17)	0.71 (±0.01)	0.63 (±0.01)	6.37 (±0.15)	2.4	2677
ZnO	14.64 (±0.14)	0.71 (±0.01)	0.64 (±0.01)	6.65 (±0.16)	2.0	3674
TiO ₂ /tBuSiOH-POM	16.20 (±0.16)	0.74 (±0.01)	0.67 (±0.01)	8.03 (±0.17)	1.8	3921
ZnO/ tBuSiOH-POM	16.35 (±0.13)	0.74 (±0.01)	0.68 (±0.01)	8.23 (±0.14)	1.5	4361

TableS4. Device characteristics of polymer solar cells having the device configuration ITO without and with tBuSiOH-POM/P3HT:IC₆₀BA/MoO_x/AI (mean values and standard deviations were extracted from a batch of 4 independent devices).

ETL	J _{sc}	V _{oc}	FF	PCE	Rs	R _{sh}
	(mA cm⁻²)	(V)		(%)	(Ω cm²)	(Ω cm²)
ITO	3.69 (±0.18)	0.25 (±0.01)	0.31 (±0.01)	0.29 (±0.20)	21.2	123
ITO/tBuSiOH-POM	9.51 (±0.14)	0.74 (±0.01)	0.60 (±0.01)	4.22 (±0.17)	3.7	1620

Table S5 Fitting parameters, obtained for P3HT 20 nm thick films (excitation wavelength: 410 nm. Detection wavelength: 700 nm) deposited on TiO₂ or ZnO substrates without and with tBuSiOH-POM.

Substrate	A ₁	τ ₁ (ps)	A ₂	τ ₂ (ps)	A ₃	τ ₃ (ps)	<τ> (ps)
TiO ₂	-	-	0.63	2.2	0.37	16	7.4
TiO₂/tBuSiOH-POM	0.47	0.32	0.53	1.91	-	-	1.2
ZnO	-	-	0.61	2.9	0.39	22	10.3
ZnO/ tBuSiOH-POM	0.31	1.5	0.37	3.2	0.32	23	9.0

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